

Application No. 09/729,882
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AMENDMENT

In the Claims

1. (twice amended) A method for manufacturing an integrated optical circuit on a substrate, the substrate having a first region and a second region distinct from the first region, the method comprising the steps of:

forming a first mask on the substrate, the first mask defining a pattern corresponding to at least one optical device to be formed in the first region of the substrate;

forming a second mask on the substrate, the second mask defining a pattern corresponding to an optical structure to be formed in the second region of the substrate; and

etching the substrate having simultaneously thereon the first and second masks, in order to form at least one optical device and the optical structure on the substrate

wherein said etching comprises using a predetermined etching gas, and said first and second masks are made of a material which substantially resists the predetermined etching gas.

Claim 4 (Currently cancelled).